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(74) Agent: **HATZMANN, M.J.**; Vereenigde, Johan de Witt-
laan 7, NL-2517 JR Den Haag (NL).

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(71) Applicant (*for all designated States except US*): **ASML NETHERLANDS B.V.** [NL/NL]; De Run 6501, NL-5504 DR Veldhoven (NL).

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(71) Applicant and

(72) Inventor: **IVANOV, Vladimir Vitalevitch** [RU/RU]; Novatorov Street, 36-3-336, Moskou, 119421 (RU).

(72) Inventors; and

(75) Inventors/Applicants (*for US only*): **BANINE, Vadim Yevgenyevich** [NL/NL]; Nierslaan 2, NL-5704 NK Helmond (NL). **KOSHELEV, Konstantin Nikolae-vitch** [RU/RU]; 4 Shkolnaya str., Troitsk, 142190 (RU). **KRIVTSUN, Vladimir Mihailovitch** [RU/RU]; Okyabrsky pr. 23-85, Troitsk, 142190 (RU).

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(54) Title: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

(57) Abstract: A lithographic system includes a source configured to generate a radiation, the source including a cathode and an anode, the cathode and the anode configured to create a discharge in a fuel located in a discharge space so as to generate a plasma, the discharge space including, in use, a substance configured to adjust radiation emission by the plasma so as to control a volume defined by the plasma; a pattern support configured to hold a patterning device, the patterning device configured to pattern the radiation to form a patterned beam of radiation; a substrate support configured to support a substrate; and a projection system configured to project the patterned beam of radiation onto the substrate.



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